Power distribution techniques for dual-VDD circuits

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- Motivation for multiple supply design
- Implications of using multiple on-chip supplies
- Power delivery
 - Board and package level issues
 - On-die power grid design
- Results and conclusions

Motivation – low power design

- Reducing power dissipation at high performance essential for: enhanced battery life in mobile applications, reduced cooling costs for workstations, improved reliability, ...
- Dynamic power dissipation in CMOS circuits α (VDD)² Static power dissipation in CMOS circuits α (VDD)³
- Quadratic/cubic savings in power if VDD scaled down
 - However, delay goes up, thus necessitating careful VDD assignment
 - \Rightarrow Multi-VDD design an important technique leveraging this

Several implications when actually implementing this idea



Multiple supply design

 Concept: Apply a lower supply (VDDL) to gates on non-critical paths thus reducing power while meeting timing



- A fine-grained VDD assignment scheme provides best power reduction
 - Extended Clustered Voltage Scaling (ECVS)
 K. Usami *et al.*, "Automated low power technique exploiting multiple supply voltages applied to a media processor," *IEEE JSSC*, 1998.
- However, physical design and power delivery are complicated

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Power delivery for dual-VDD circuits

- Fine-grained dual-VDD places VDDL/VDDH gates arbitrarily on the die
- Dual-VDD circuits need to supply two on-die voltages
 - Wire congestion
 - Power grid integrity
- Board and package level issues
 - Fixed resources need to be split between VDDL and VDDH
- However, load on each supply lower than on original single supply, allowing robust power delivery within available resources (fixed decap, C4, wiring)

VDD assignment and power savings

 A large number of gates go to the lower supply in a dual-VDD optimized netlist

	VDDL	= 0.8V	VDDL = 0.6V		
	% Savings	%VDDL	% Savings	%VDDL	
c880	28	65	31	55	
c2670	32	65	37	56	
c5315	35	58	37	49	
c7552	44	91	49	71	



Avg. 70% (58%) for VDDL = 0.8V (0.6V) with respect to original single VDD design (1.2V)

Current drawn from VDDL/VDDH

Current drawn at gate level

	Single-VDD		Dual-VDD	: VDDL=0.8V	Dual-VDD: VDDL=0.6V		
	Low-VTH	High-VTH	Low-VTH	High-VTH	Low-VTH	High-VTH	
INVX10	1.00	0.90	0.57	0.49	0.36	0.27	
NAND2X2	1.00	0.85	0.54	0.45	0.34	0.23	
NAND3X6	1.00	0.88	0.55	0.47	0.35	0.24	
NOR2X1	1.00	0.86	0.52	0.39	0.30	0.19	
NOR3X4	1.00	0.85	0.50	0.37	0.29	0.18	



□ Avg. 54% (33%) for VDDL = 0.8V (0.6V)

Current drawn at circuit level

	Single VDD	Dual VDD	: VDDL=0.8V	Dual VDD: VDDL=0.6V		
	VDD	VDDH	VDDL	VDDH	VDDL	
c880	9.7	5.6	2.2	5.9	1.3	
c2670	23.6	11.9	6.5	10.1	3.0	
c5315	36.7	20.9	7.2	20.9	3.6	
c7552	47.9	13.9	19.4	20.4	8.5	



Avg. 49% (51%) and 28% (14%) for VDDH and VDDL for 0.8V (0.6V)

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Board and package level study



Intel, "Intel Pentium 4 processor in the 432 pin/Intel 850 Chipset Platform," 2002.

Package level results

- Two VRMs on board to supply VDDL and VDDH
- Ground path can be shared by VDDL and VDDH
- Decoupling capacitance divided in the ratio of current loads



 Similar power supply noise with same resources (decap, C4) as single-VDD case

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Segregated placement constrains placer leading to higher core-area and wirelength

C. Yeh, *et al.*, "Layout techniques supporting the use of dual supply voltages for cell-based designs," *Proc. DAC*, 1999. M. Igarashi, *et al.*, "A low-power design method using multiple supply voltages," *Proc. ISLPED*, 1997.

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Unconstrained dual-VDD placement





Grid texture



Dual-VDD power grid design

Important while designing the dual-VDD grid:

- Scale wires with respect to the single-VDD considering how the current demand has scaled
- □ VDDL gates more sensitive to grid noise ⇒ important as ground is shared
 - 120mV noise is 10% for a 1.2V gate, but 15% for a 0.8V gate
 - 7% higher delay for a 1.2V gate, but 16% for a 0.8V gate
- □ Placement of VDDL and VDDH gates ⇒ assign more wiring resources to VDDL grid in areas where there is more demand for VDDL current
- Consider effects that arise from the board and package level such as shared C4s
 - Fewer C4s leads to higher effective package R, L

Proposed technique (D-Place)

- Let $\alpha = I(VDDH)/I(VDD)$ and $\beta = I(VDDL)/I(VDD)$
- Scale wires as follows $W_{VDDH} = \alpha W$

$$W_{VDDL} = \beta \frac{VDDH}{VDDL} W$$

$$W_{VDDL} = (\alpha + \beta) \frac{VDDH}{VDDH}$$

$$W_{GND} = \left(\alpha + \beta\right) \frac{VDDH}{VDDL} W$$

Partition the chip floorplan



Design flow



Prior work

- Dual-VDD and Dual-GND:
 - Requires two separate grounds off-chip
 - Complicates timing analysis and design of the board
 - □ M. Popovich et al., GLVLSI, 2005.

• (DVDG)

- Dual-VDD and Shared-GND:
 - □ C. Yeh *et al.*, *DAC*, 1999
 - D-Vanilla)

Dual-VDD	Dual-GND
└── VDDH └── GNDH	UDDL



- 3-D PEEC model
- Wires fractured and represented by RLC models
- Modeled area about 0.5mm² (600,000 R/L/C elements)

C. Hoer and C. Love, "Exact inductance equations for rectangular conductors with applications to more complicated geometries," *J. Res. Nat. Bureau Stds.*, 1965.

S. C. Wong, *et al.*, "Modeling of interconnect capacitance, delay and crosstalk in VLSI," *IEEE Trans. Sem. Manuf.*, 2000.

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Peak voltage drop comparisons

VDDL = 0.6V

VDDL = 0.3	8V
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		Single VDD	DVDG	D-Vanilla	D-Place			Single VDD	DVDG	D-Vanilla	D-Place
	MAX	16.9%	30.9%	16.4%	18.6%		MAX	16.9%	30.3%	16.3%	19.5%
c880	AVG	9.5%	14.7%	9.6%	9.5%	c880	AVG	9.5%	15.9%	9.7%	9.8%
	MAX	25.6%	35.5%	32.2%	25.5%		MAX	25.6%	36.1%	27.6%	27.0%
c2670	AVG	15.9%	19.8%	15.2%	14.5%	c2670	AVG	15.9%	22.1%	15.8%	15.3%
	MAX	29.6%	38.2%	37.4%	32.0%		MAX	29.6%	38.1%	33.0%	31.8%
c5315	AVG	21.6%	23.4%	20.2%	19.8%	c5315	AVG	21.6%	25.4%	20.1%	20.3%
	MAX	26.8%	34.2%	34.5%	29.4%		MAX	26.8%	31.4%	31.6%	28.7%
c7552	AVG	22.2%	21.0%	21.1%	18.7%	c7552	AVG	22.2%	24.9%	22.3%	20.1%

- D-Place similar to single-VDD grids in AVG cases
- Inferior by < 2.6% (≈15mV) in some MAX cases</p>
- 0.6V VDDL as robust as 0.8V
- 0.6V also provides higher power savings
- Proposed approach better by 2-7% (AVG) and 7-12% (MAX) compared to prior approaches

Voltage variation across die



Additional comparison metrics

Wire congestion

	Single	DVDG		D-Va	nilla	D-Place		
	VDD	0.6V	0.8V	0.6V	0.8V	0.6V	0.8V	
c880	0.17	0.17	0.17	0.19	0.20	0.17	0.16	
c2670	0.17	0.17	0.17	0.19	0.20	0.16	0.16	
c5315	0.17	0.17	0.17	0.19	0.20	0.18	0.16	
c7552	0.17	0.17	0.17	0.19	0.20	0.15	0.15	

 Comparable to single-VDD as wires are scaled in proportion to lowered current demand

Maximum voltage variation across die

	Single	DVDG		D-Va	nilla	D-Place		
	VDD	0.6V	0.8V	0.6V	0.8V	0.6V	0.8V	
c880	10.4%	24.5%	21.1%	11.2%	11.0%	13.8%	13.5%	
c2670	14.9%	26.6%	25.2%	26.3%	22.4%	18.7%	19.7%	
c5315	13.7%	28.2%	23.8%	28.4%	22.6%	21.9%	20.2%	
c7552	10.8%	19.9%	16.3%	24.5%	23.9%	19.1%	18.3%	

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- Demonstrated the feasibility of power delivery for dual-VDD circuits
- Leveraged the observation that dual-VDD circuits have significantly lower supply current demands
- Addressed board and package level issues
- Proposed an improved method for designing on-die grids





Simulation setup

- CMOS process: 1.2V, 0.13µm, dual-Vth, 6 metal layers
- Voltage assignment scheme:
 - Fine-grained (ECVS) based algorithm
 - Asynchronous level converters used
- VDDL = {0.6V, 0.8V}
- VDDH = 1.2V (nominal)
- Standard cell row based layout using Cadence SE



Scaled decap

	Scaled Decap Dual VDD					
Decoupling	Decap (VDDH)	1.02nF (1.06nF)				
Capacitance	Decap (VDDL)	0.91nF (1.30nF)				
	Total Decap	1.93nF (2.36nF)				
Grid						
integrity	MAX	27.6% (27.0%)				
metrics	AVG	16.9% (15.3%)				

Dual-VDD level conversion and VDD assignment references

S. H. Kulkarni and D. Sylvester, "High performance level conversion for multi-VDD design," *IEEE TVLSI*, 2004. S. H. Kulkarni, *et al.*, "A new algorithm for improved VDD assignment in low power dual VDD systems," *ISLPED*, 2004.